

Fig. 1

Fig. 2A

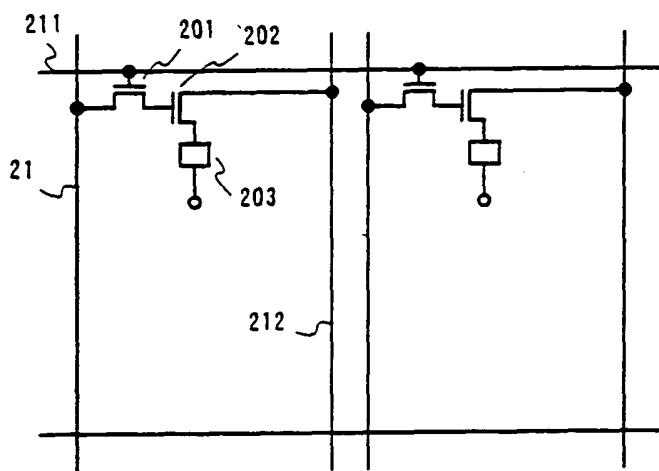
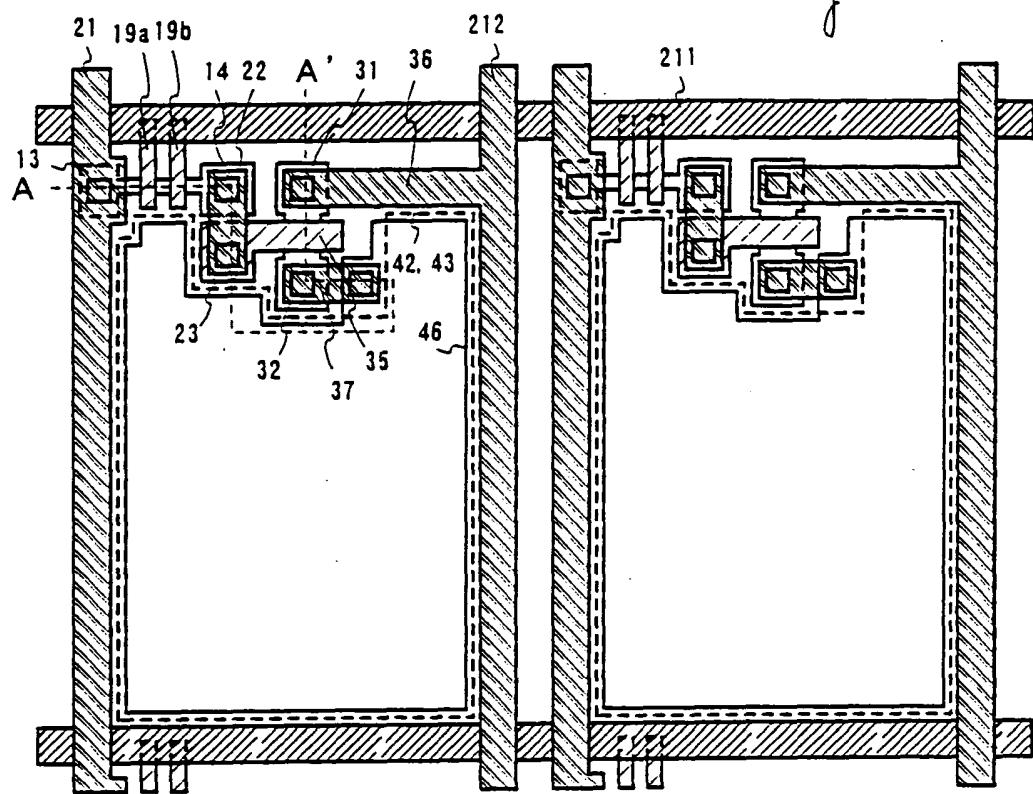


Fig. 2B

Fig. 3A CRYSTALLIZATION STEP

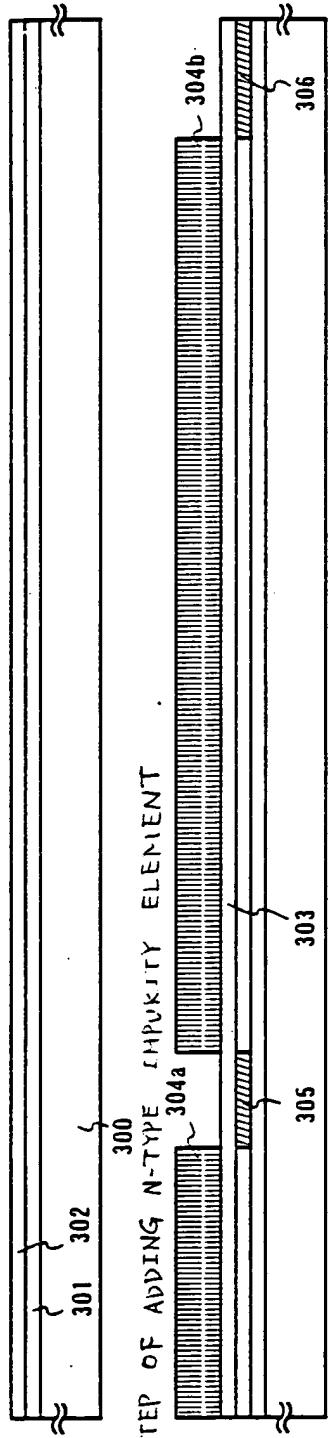


Fig. 3B

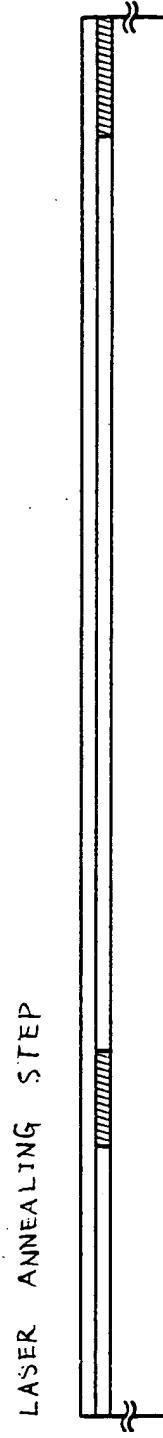


Fig. 3c

Fig. 3D

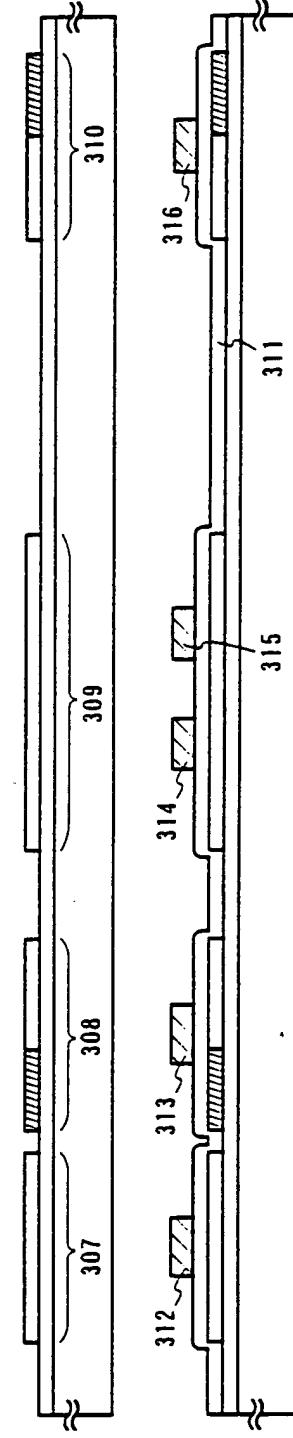


Fig. 3E

STEP OF ADDING N-TYPE IMPURITY ELEMENT

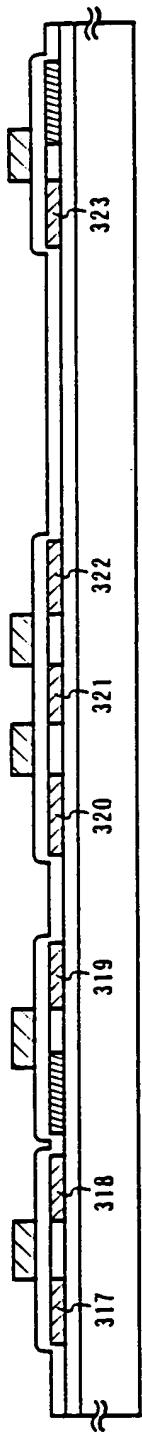


Fig. 4A

STEP OF ADDING N-TYPE IMPURITY ELEMENT

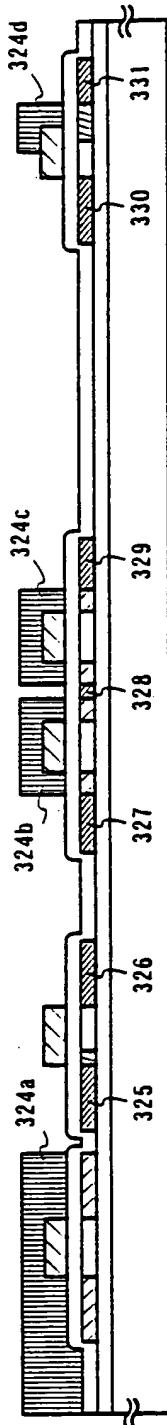


Fig. 4B

STEP OF ADDING P-TYPE IMPURITY ELEMENT

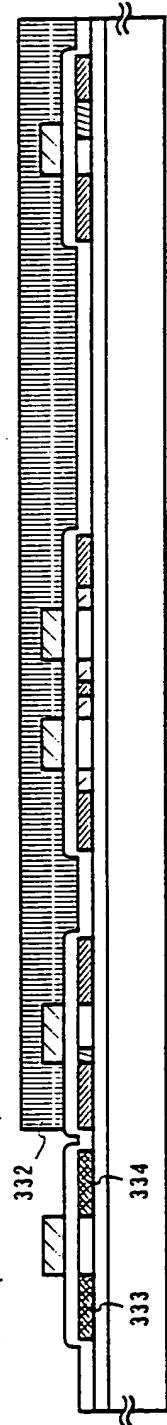


Fig. 4C

330

331

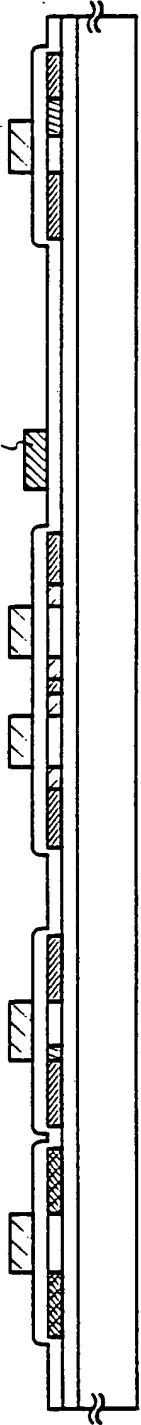
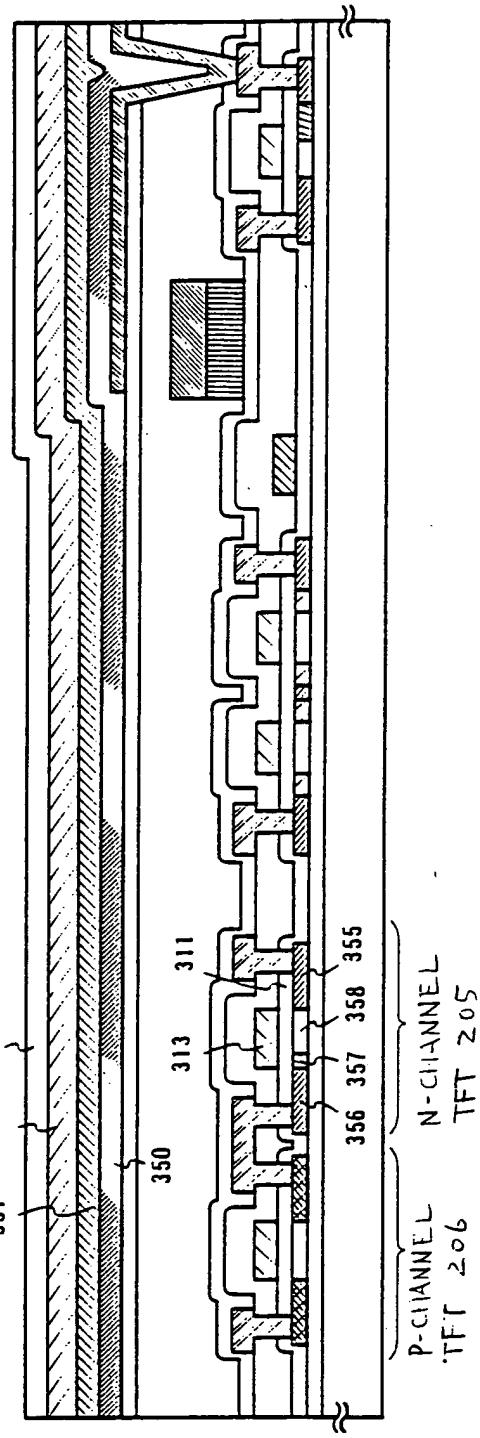
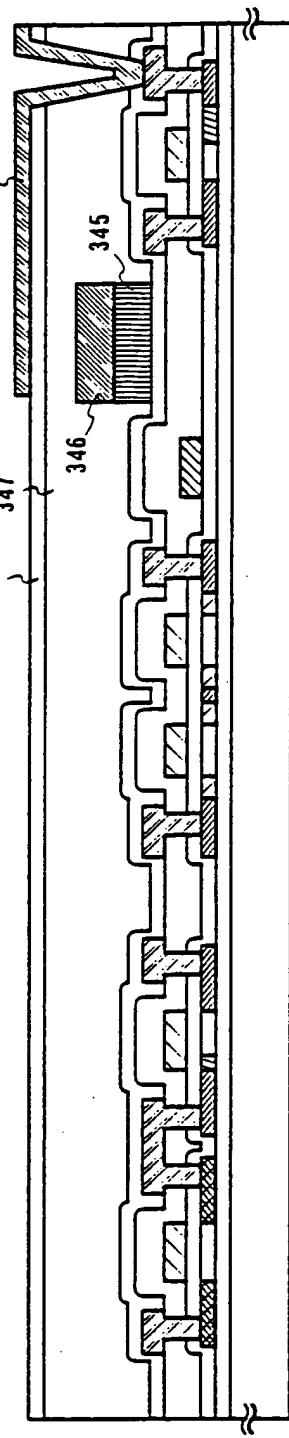
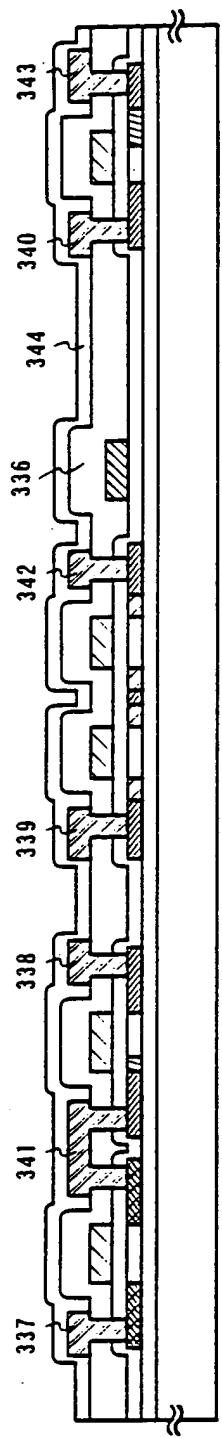
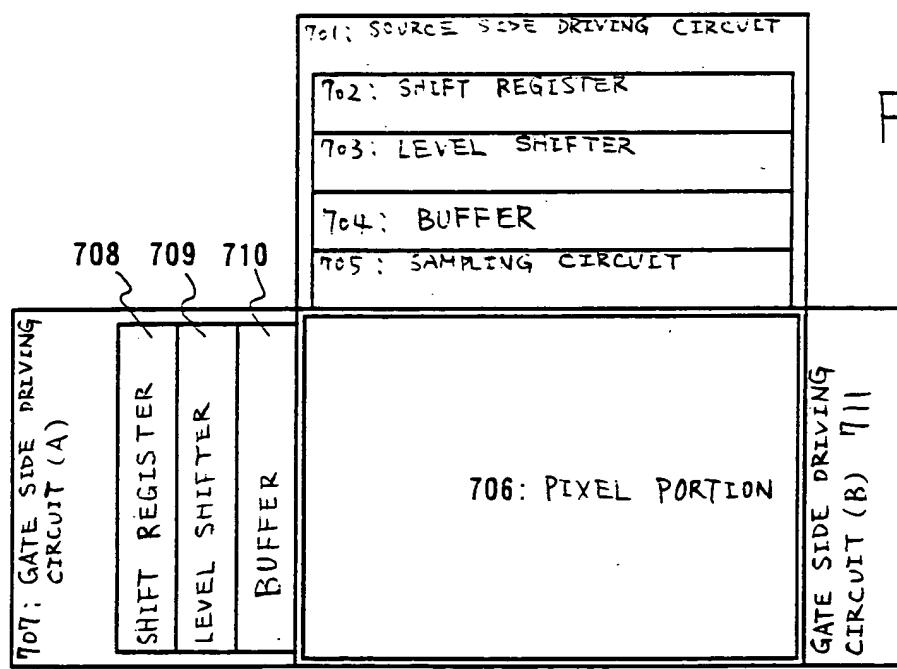
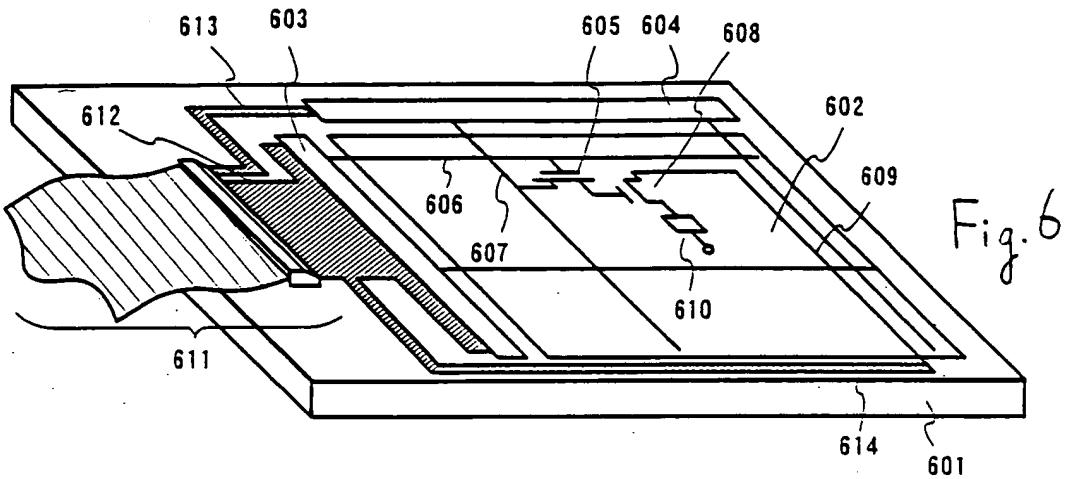


Fig. 4D





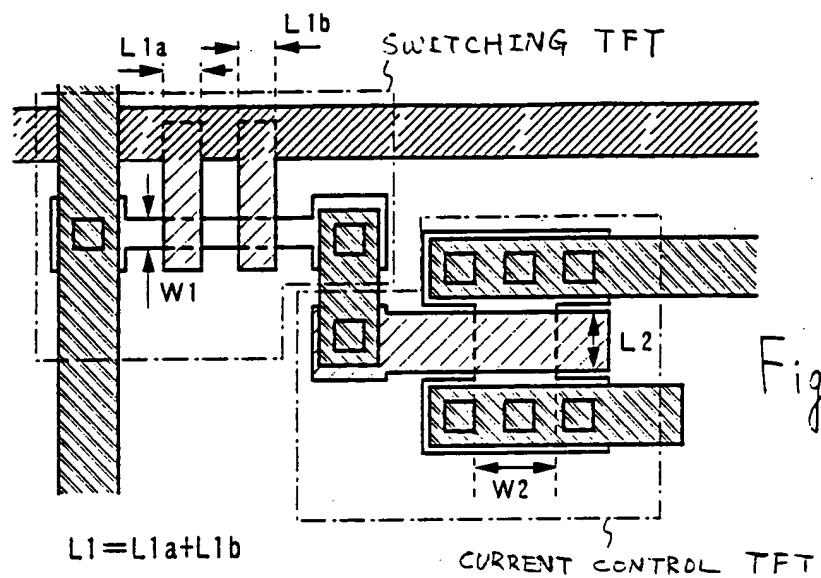


Fig. 8

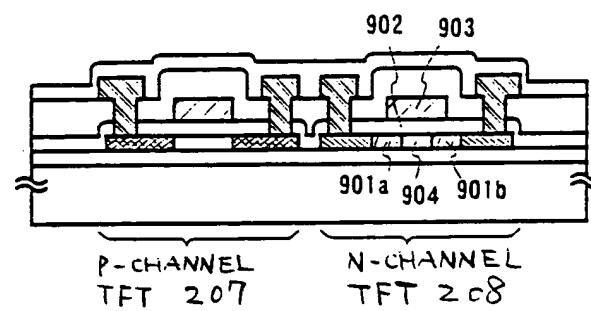


Fig. 9

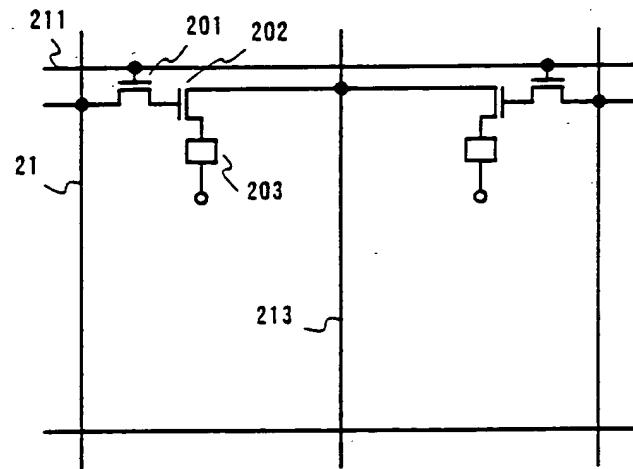
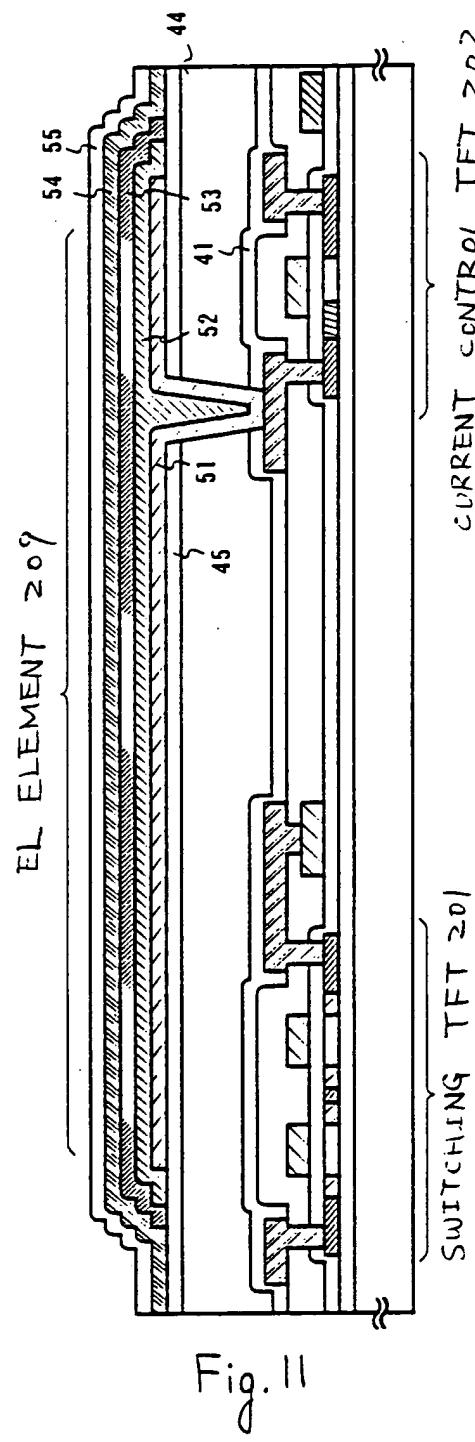


Fig. 10



CURRENT CONTROL TFT 202

Fig. 12A

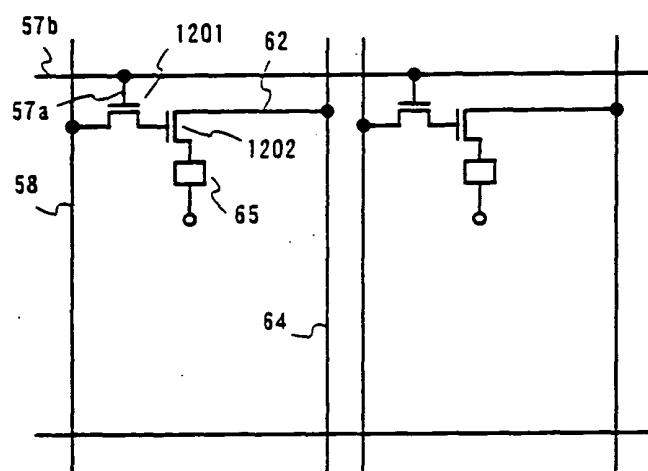
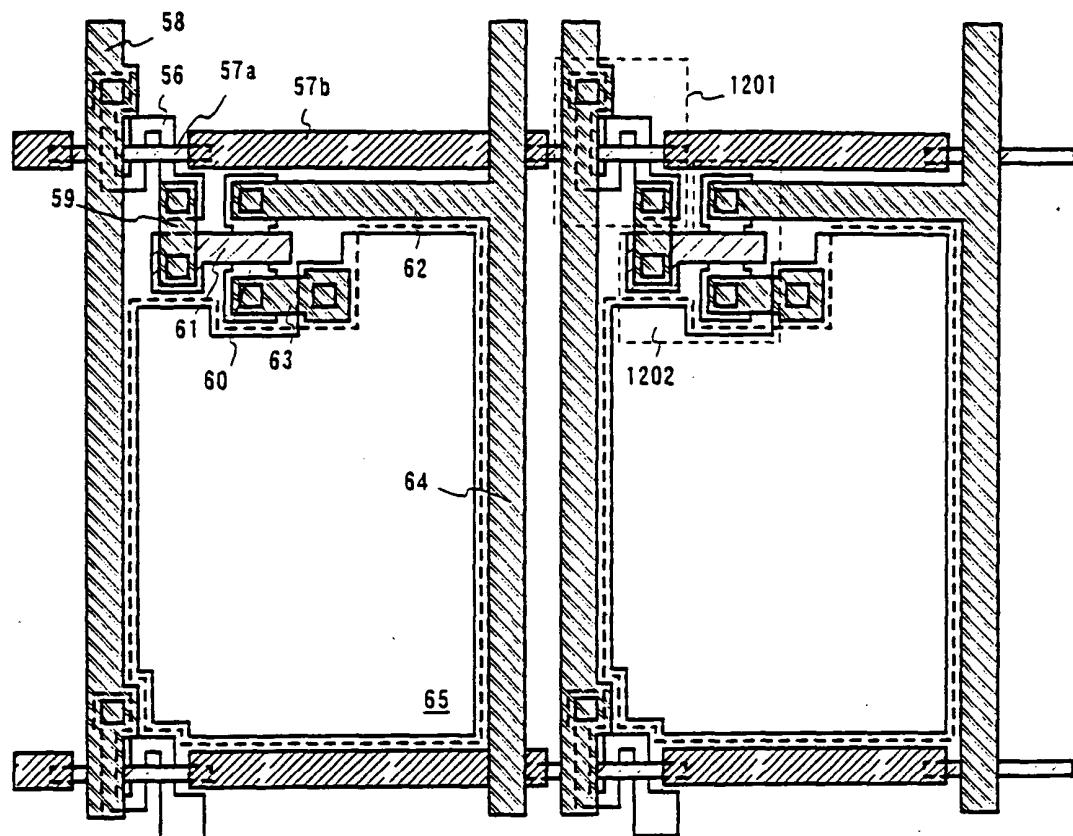
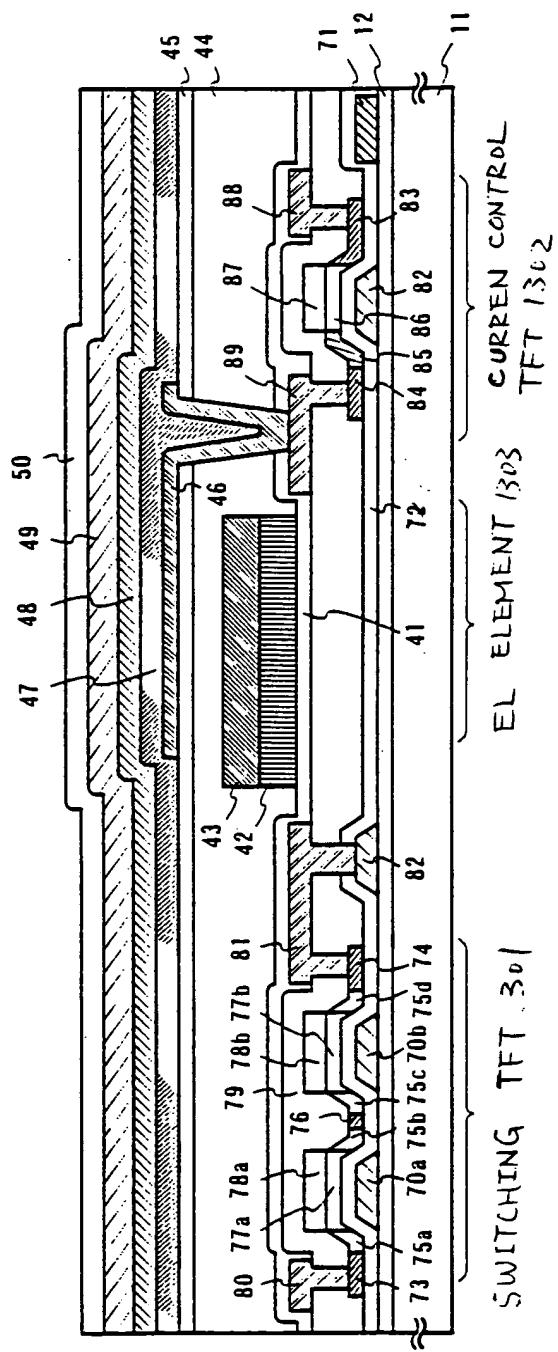
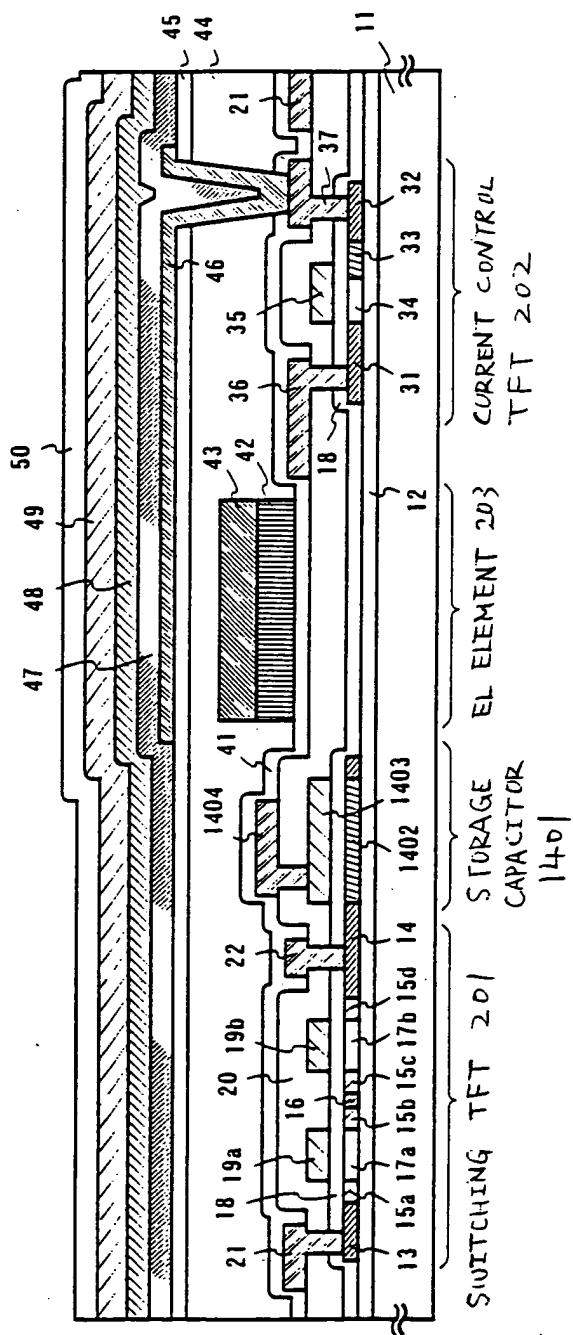


Fig. 12B



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Fig. 15A

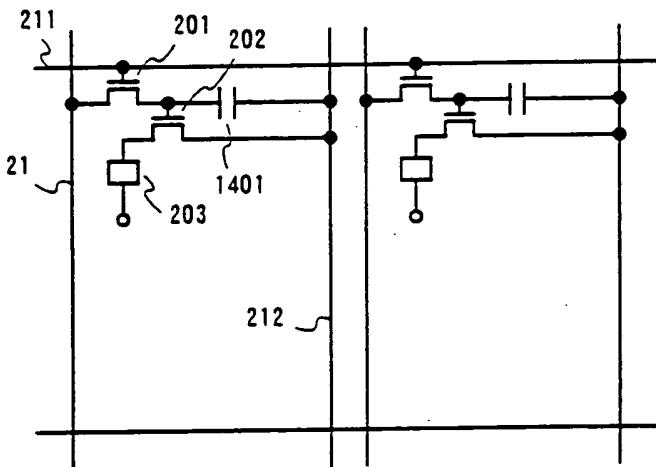
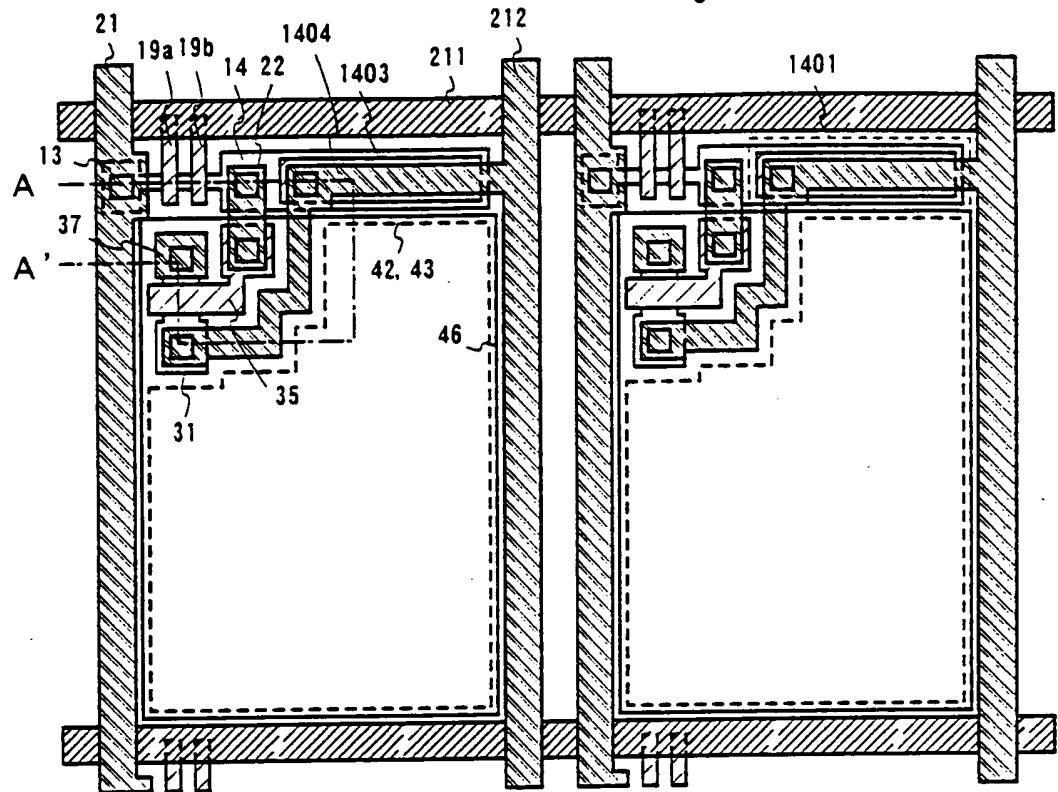
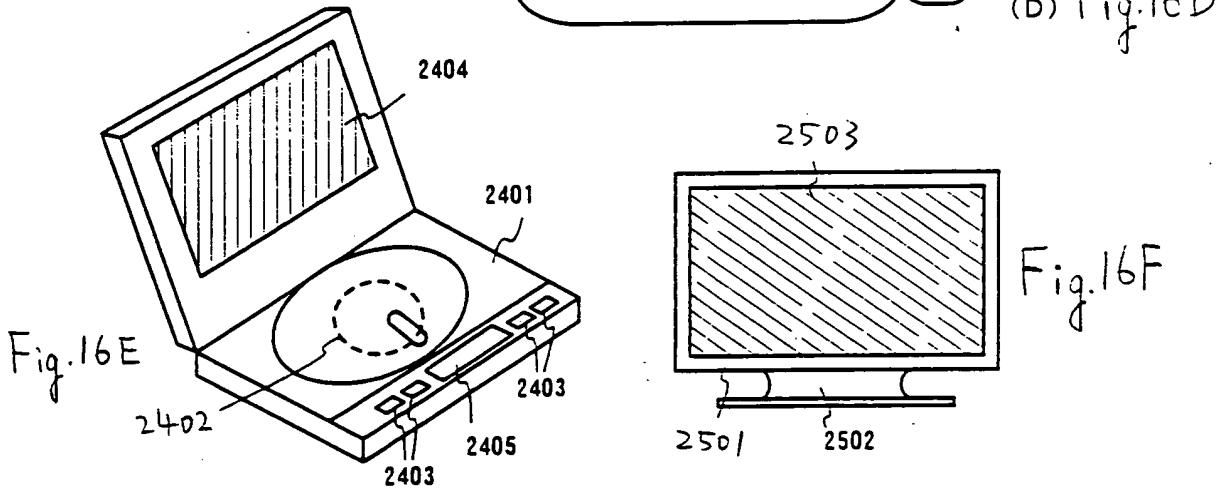
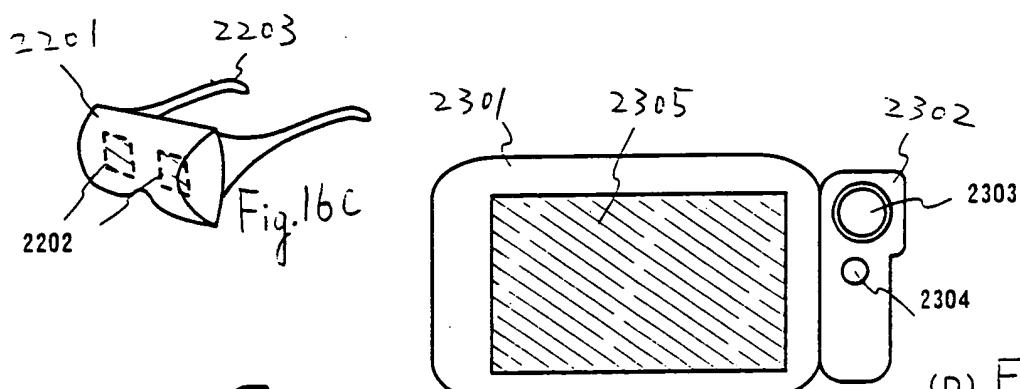
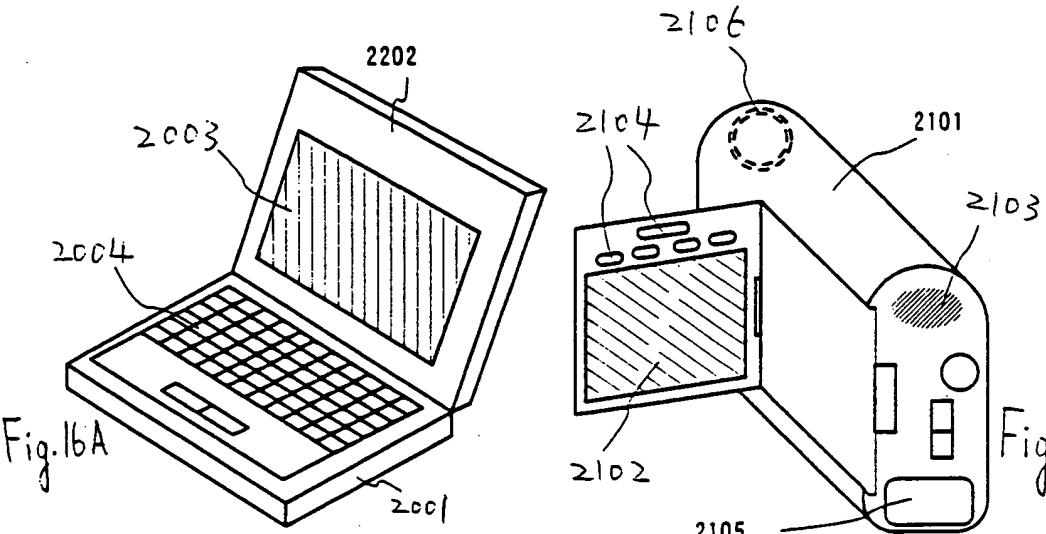


Fig. 15B



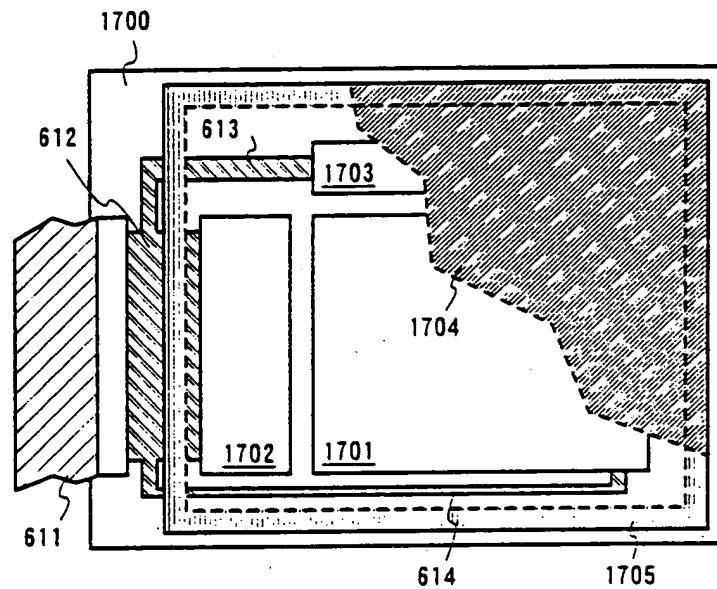


Fig. 17A

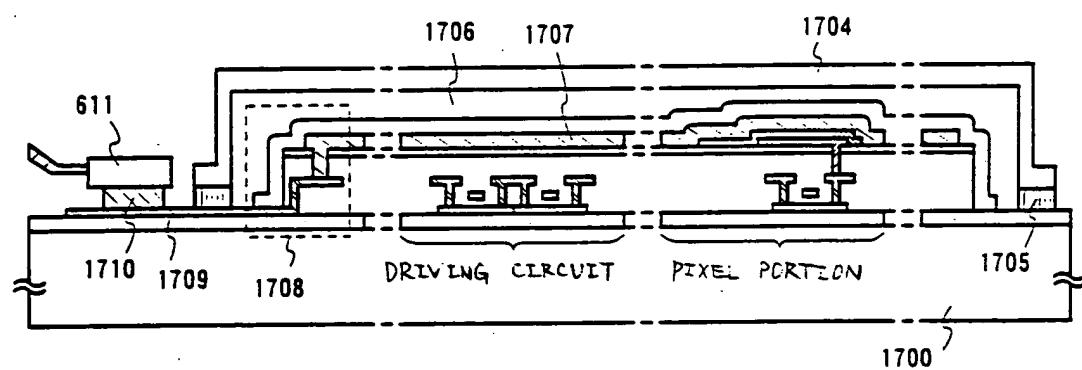


Fig. 17B

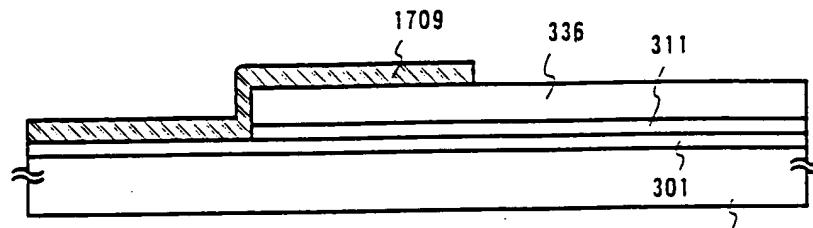


Fig. 18A

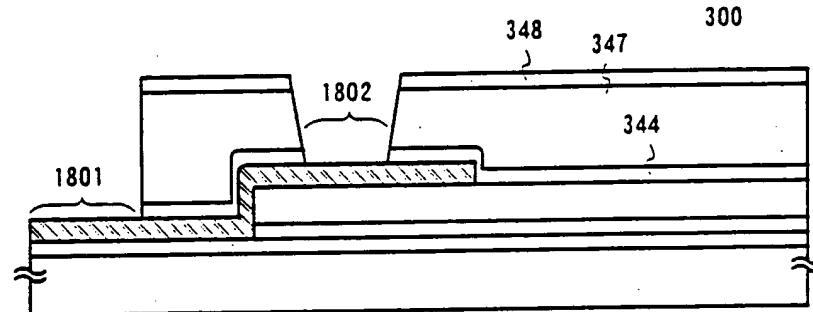


Fig. 18B

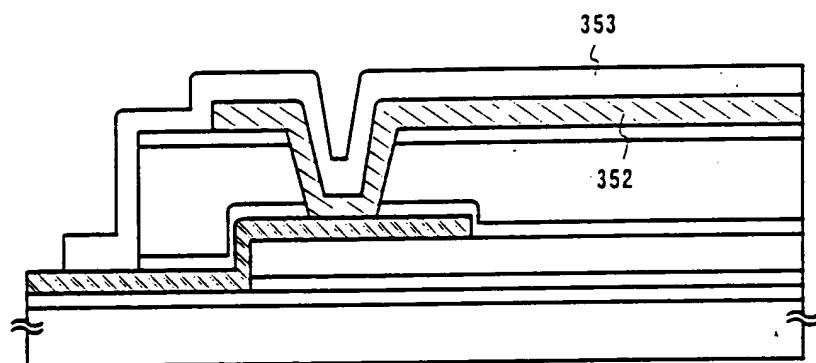


Fig. 18C

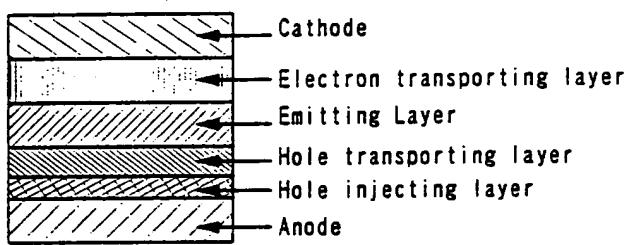


Fig.19

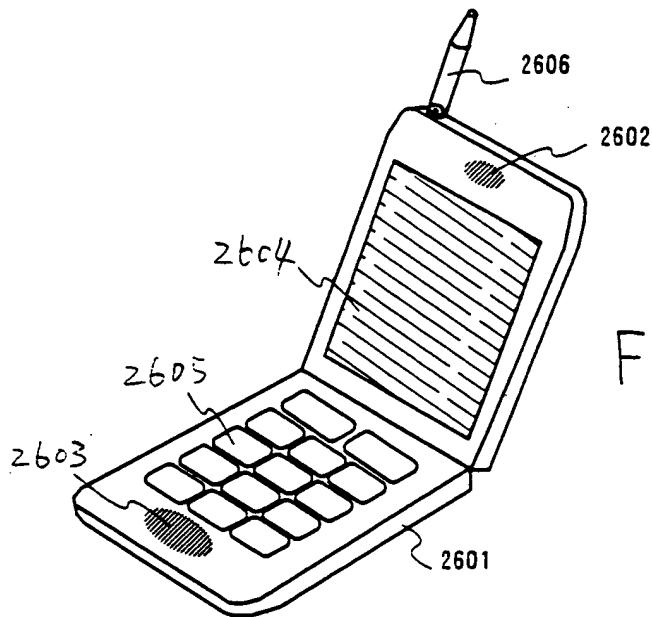


Fig. 20A

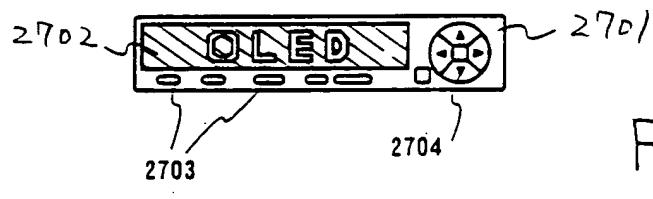
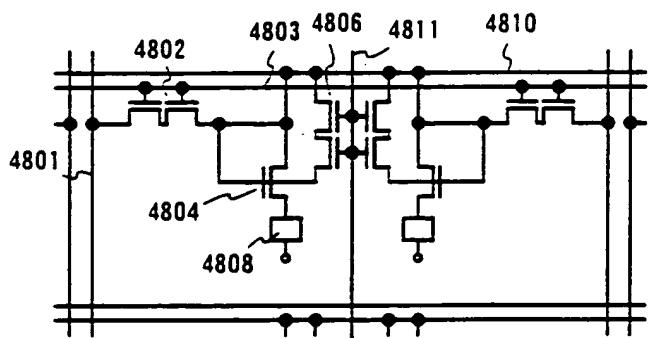
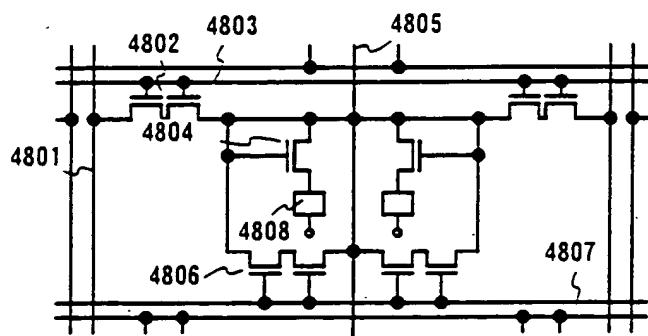
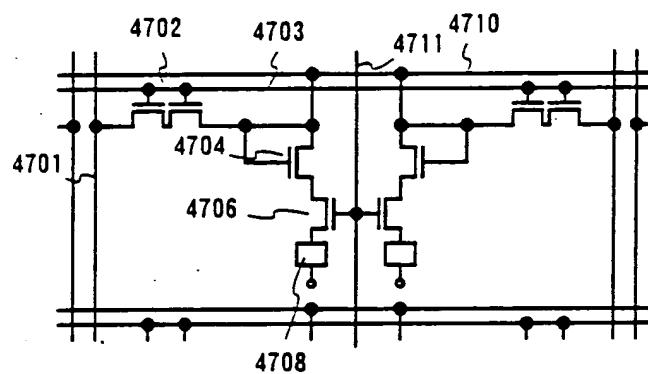
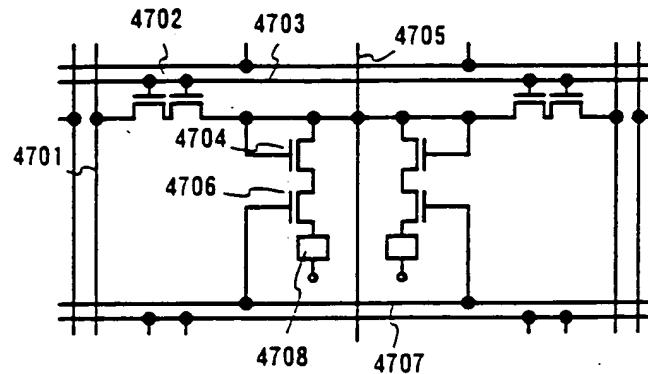


Fig. 20B



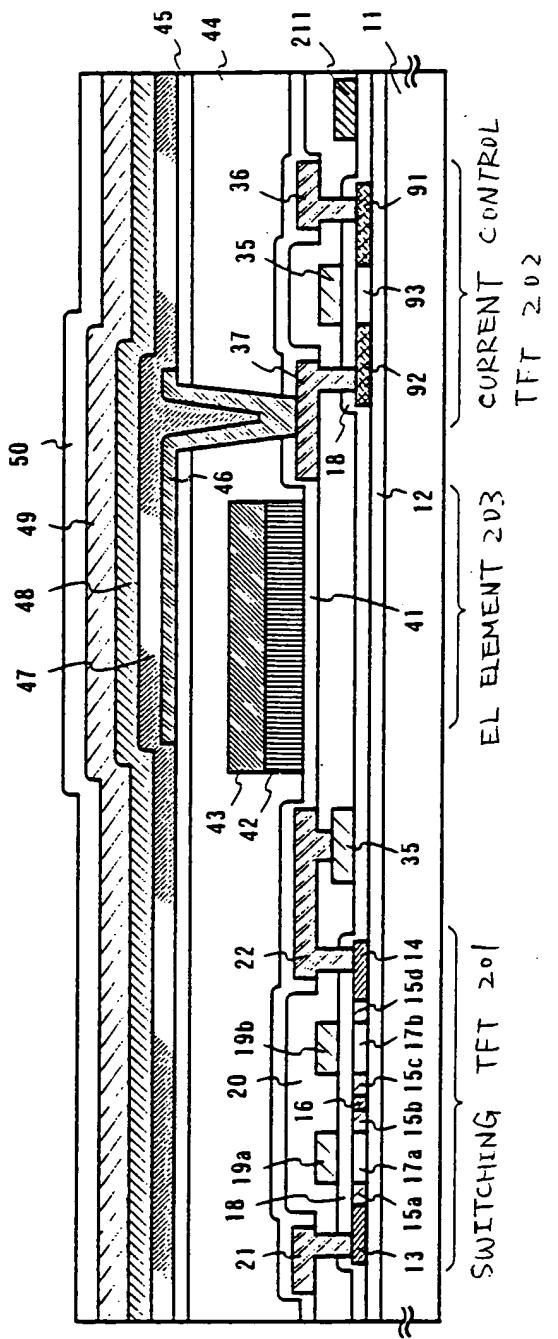


Fig. 23